	Hits	Search Text	DBs
22	2	((resist or photoresist or photosensitive or radiation$4sensitive or photocur$4) same (uniform$3 or thin$4 or etch$4) same micron) and (((photo$4active$4acid$4generat$4 or (photoacid near5 (liberat$4 or generat$4)) or (acid near5 (liberat$4 or generat$4)) or PAG or photo$8generat$4) near9 (increas$4 or var$5 or chang$4 adjust$4 or alter$4 or control$4)) same (moiet$4 or group or (function$3 near4 group))) and ((fluoro$4polymer$4 or ((fluor$4 or halogen) near9 (polymer or carbon)) or (SOG near6 (organic or resist))) same (pattern$4 or lithograph$6 or photolithograph$8 or expos$4 or mask))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
23	46	((resist or photoresist or photosensitive or radiation$4sensitive or photocur$4) same (photo$4active$4acid$4generat$4 or (photoacid near5 (liberat$4 or generat$4)) or (acid near5 generat$4) or PAG or photo$8generat$4) same (coat$4 or spin$4coat$4 or deposit$4) same (uniform$3 or thin$4 or etch$4) same (resolution or imag$4 or thickness or micron)) and (((photo$4active$4acid$4generat$4 or (photoacid near5 (liberat$4 or generat$4)) or (acid near5 (liberat$4 or generat$4)) or PAG or photo$8generat$4) near9 (increas$4 or var$5 or chang$4 adjust$4 or alter$4 or control$4)) same (moiet$4 or group or (function$3 near4 group)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB